

SYSTEM, METHOD AND COLLIMATOR FOR OBLIQUE DEPOSITION

ABSTRACT OF THE DISCLOSURE

5 A deposition system and method for creating tilted thin films
with azimuthal symmetry by oblique deposition. The deposition system
includes a collimator for use with physical vapor deposition to provide control
of the angle of incidence of the flux with improved flux throughput compared to
conventional oblique deposition techniques. Additionally, the deposition system
includes a collimator that may be used as a vacuum barrier for reduction of
10 thermalization near the substrate.

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